Abstract of the Disclosure

The method of forming a Si-containing thin film forms a film using an organic Si-containing compound having a Si-Si bond represented by the following formula (I):

$$(R^{2})_{2}N$$
 $(R^{1})-S i-S i-(R^{1})$
 $(R^{2})_{2}N$
 $N(R^{2})_{2}$
 $N(R^{2})_{2}N$
 $N(R^{2})_{2}$

wherein R^1 represents a hydrogen or a methyl group, and R^2 represents a methyl group, an ethyl group, a propyl group or a tertiary butyl group.